

REMARKS

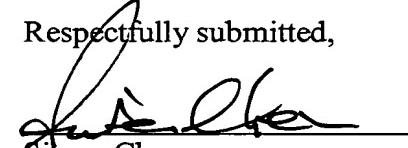
The present application is technically related to U.S. Patent Application Serial No. 09/920,227, filed by Laural J. Ball et al. on August 1, 2001, entitled "Method for Making Photomask Material by Plasma Induction."

The undersigned attorney is granted limited recognition by the Office of Discipline and Enrollment of the USPTO to practice before the USPTO in capacity as an employee of Corning Incorporated. A copy of the document granting such limited recognition either has been previously submitted or is submitted herewith for the record.

Please direct any questions or comments to the undersigned at (607) 248-1253.

DATE: February 23, 2004

Respectfully submitted,



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